



Socket No.: 200062US0XPCT

RECEIVED
APR 3 8 2003
TC 1700

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

Kenichi HIROTA, et al. : GROUP ART UNIT: 1746

SERIAL NO: 09/700,704 :

FILED: NOVEMBER 24, 2000 : EXAMINER: KORNAKOV, M.

FOR: CLEANING SOLUTION AND CLEANING METHOD FOR COMPONENT OF
SEMICONDUCTOR PROCESSING APPARATUS

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

In response to the Office Action mailed October 2, 2002, Applicants request
reconsideration of the above-identified application in view of the following amendment and
remarks.

IN THE CLAIMS

Cancel Claims 13-18.

Please amend the claims as follows:

Sub C D
1. (Twice Amended) A cleaning solution for removing a byproduct derived from a
decomposed substance of a process gas containing C and F, and deposited on a component in
a process chamber of a semiconductor processing apparatus for subjecting a target substrate
to a semiconductor process with the process gas, the cleaning solution comprising N-methyl-
2-pyrrolidone, ethylene glycol monobutyl ether, a surfactant, and water.

B 1
3. (Twice Amended) The cleaning solution according to claim 1, wherein the water
concentration is 5 to 20 wt%.